

Microsystems Based on Wide Band Gap Materials for Future
Space Transmitting Ultra Wideband Receiving Systems

SATURNE

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Materials for Future Space Transmitting
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A. ZIAEI
THALES Research & Technology

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SATURNE: Microsystems Based on Wide Band Gap Materials for Future Space Transmitting Ultra Wideband Receiving Systems

Project number: 242458

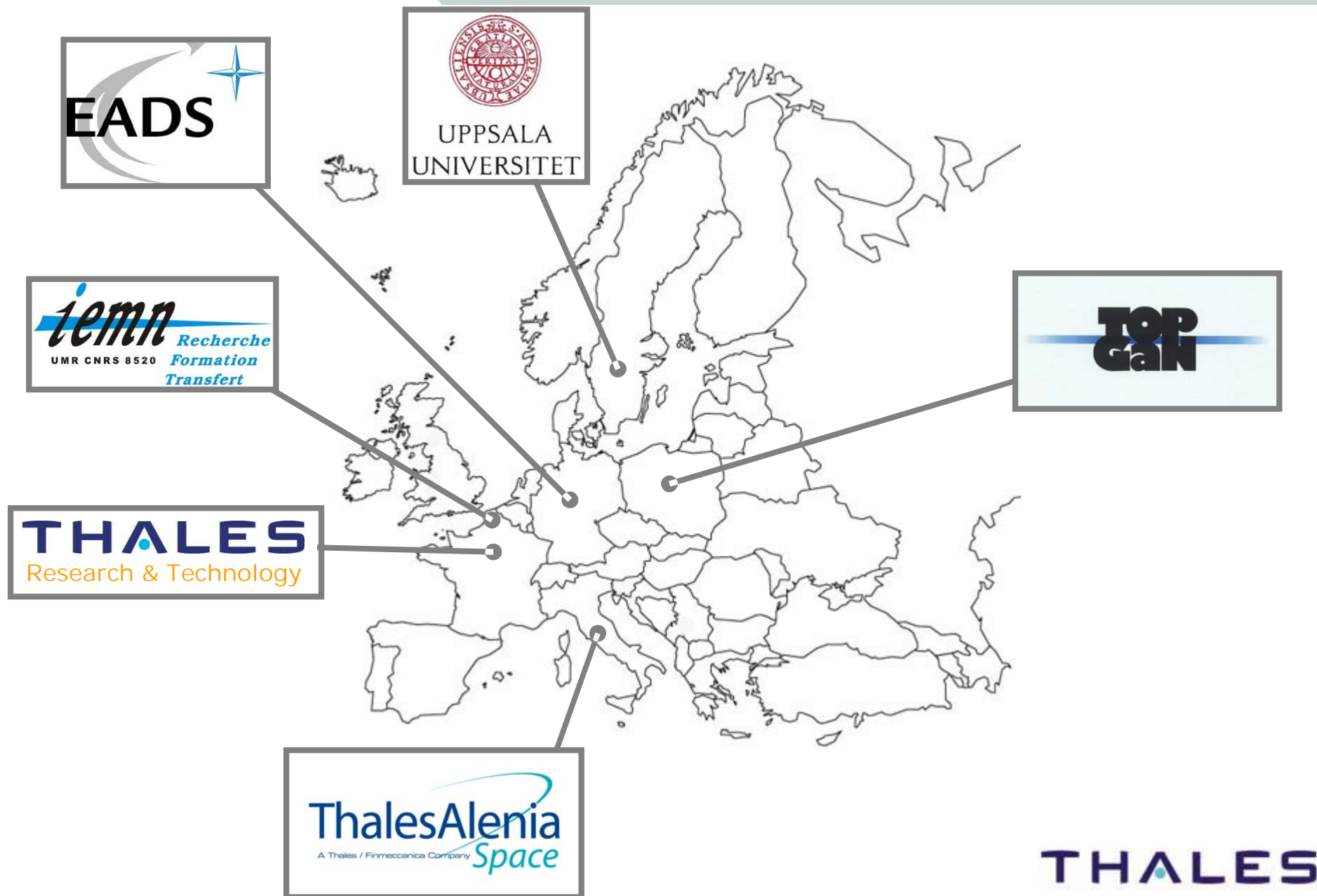
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FP7-SPACE-2009-1

Work programme topics addressed

- u **Activity 9.2** Strengthening the foundations of Space science and technology
- u **Area 9.2.2** Research to support space transportation and key technologies
- u **SPA.2009.2.2.01** Space technologies



Integration of WBG devices and RF-MEMS

- u **Monolithic integration approach**
- u **Hybrid integration approach**
- u **Hybrid and monolithic integration approaches**

1st demonstrator: Smart active antenna based on WBG devices and RF-MEMS

2nd demonstrator: A miniaturized reconfigurable front-end

3rd demonstrator: Re-configurable frequency-agile T/R module

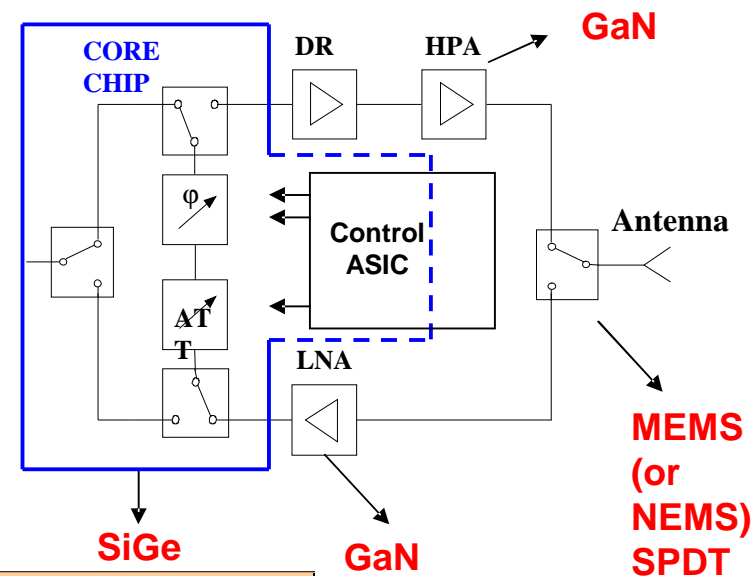
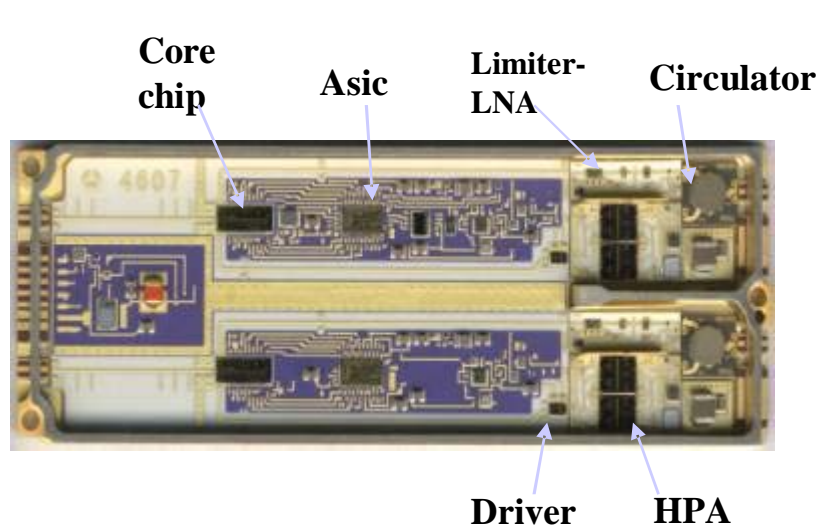
Monolithic integration approach

- u **Assessment and compatibility of RF-MEMS fabrication process and GaN technology**
- u **An elementary device, a GaN based RF-MEMS switch, will be developed with the following specifications:**
 - £ Frequency range: 2-20 GHz
 - £ Power handling: 10 W (40 dBm)
 - £ Isolation: -20 dB
 - £ Insertion loss: -0.4 dB
- u **GaN-based-MEMS-RF subsystems: Single Pole Double Throw (SPDTs)**
- u **Feasibility of a production process of these components compatible with the integration of both MMICs and RF-MEMS functions onto the same substrate will be evaluated**

▷ **1st demonstrator: Smart active antenna based on WBG devices and RF-MEMS**

Context, SoA & Goals

u GaN devices for microwave applications



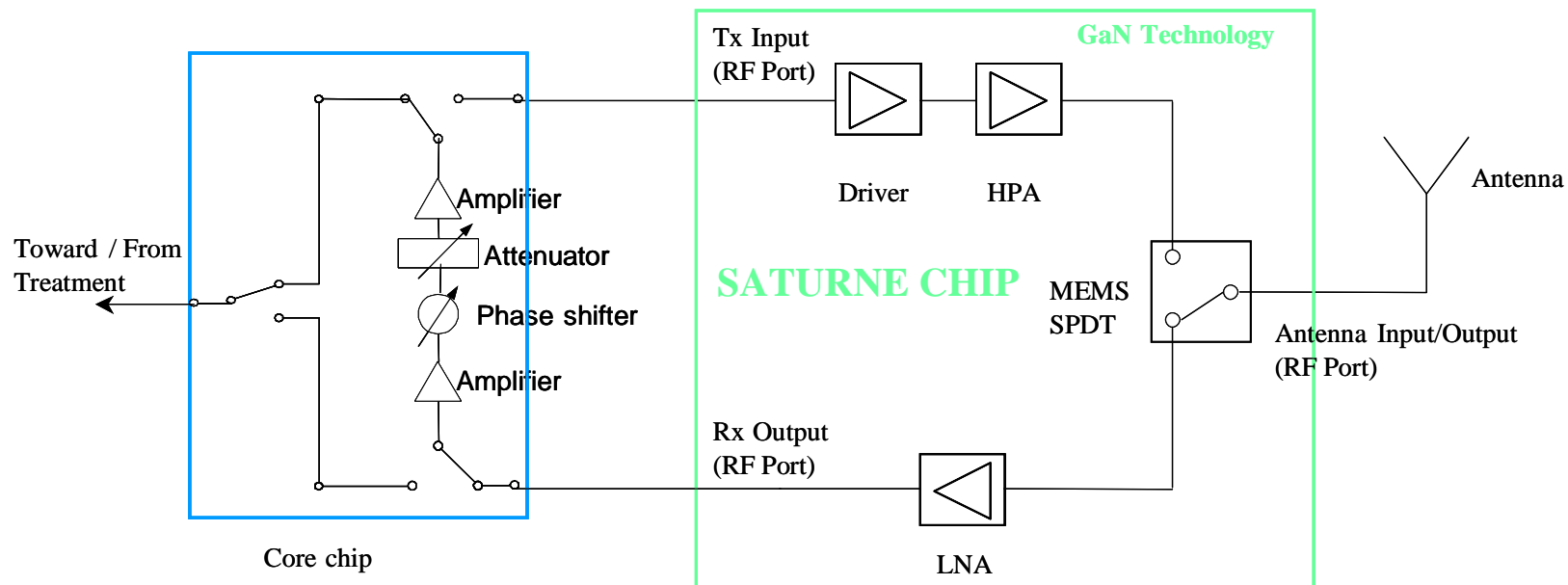
		short-term solution	mid-term solution
HPA	S-band	Si BJT -> GaAs HBT	GaN HEMT
	X-band	GaAs HBT, P-HEMT	GaN HEMT
	C-Ku band	GaAs P-HEMT	GaN HEMT
Core-chip	all bands	GaAs P-HEMT	SiGe
LNA	all bands	GaAs P-HEMT	GaN HEMT
T/R Switch	all bands	Circulator	Power MEMS

< 5 years

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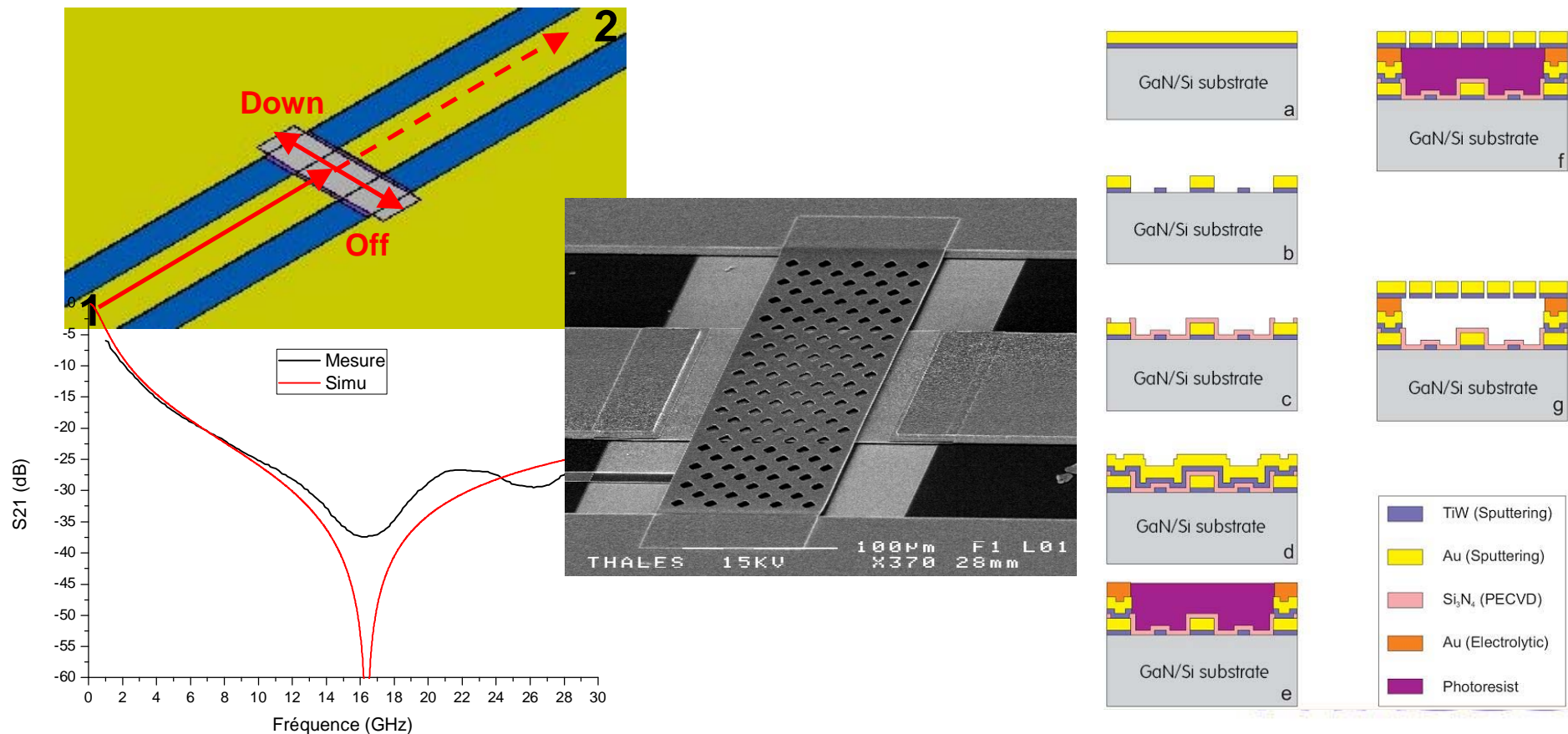
Demonstrator #1 (Thales Research & Technology)
High Power T/R module
Monolithic integration of GaN technologies

- u **GaN-based HPA & LNA (20W X-Band)**
- u **GaN-based RF-MEMS SPDT**



Monolithic integration of RF-MEMS on GaN

- u Shunt RF-MEMS on GaN/Si (Dielectric: PZT or TiO₂)
- u Next step: integration with GaN HEMT



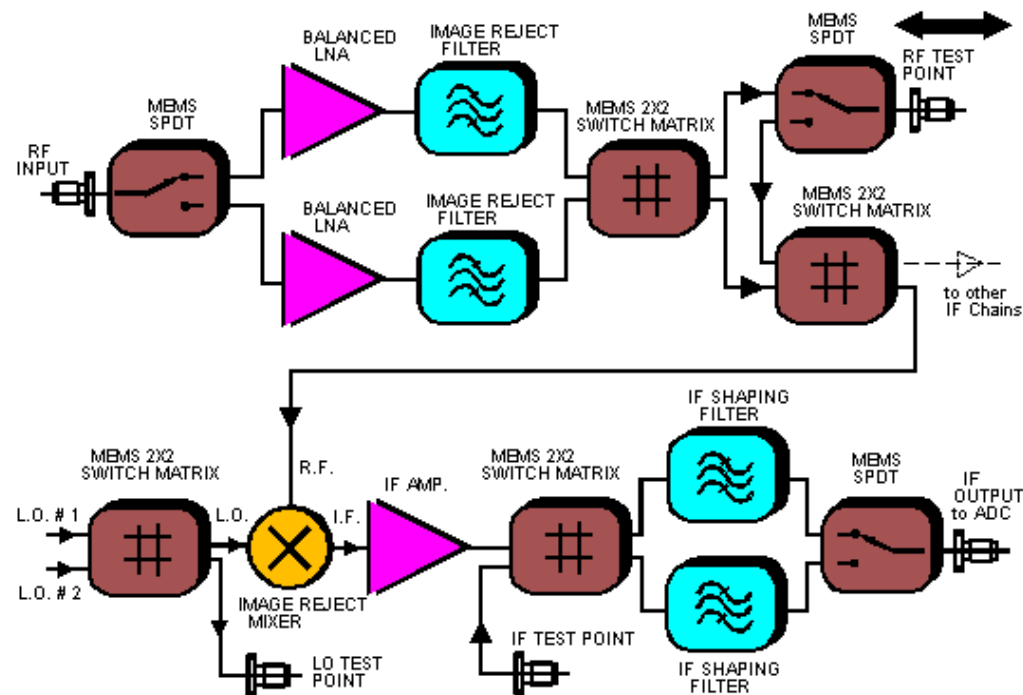
Hybrid integration approach

- u **Feasibility and performance of re-configurable RF-MEMS based matching networks for GaN power and low-noise transistors by using a hybrid integration approach of both technologies**
- u **RF-MEMS switches will be integrated on LTCC multilayer substrates**
 - £ RF-MEMS switches on LTCC
 - £ RF-MEMS SPDTs and 2x2 switch matrices on LTCC

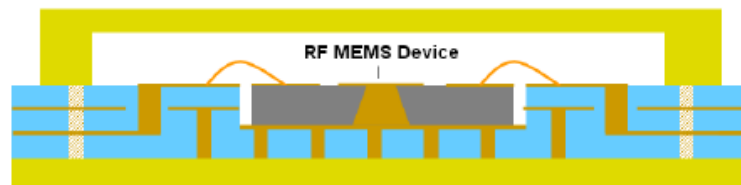
▷ **2nd demonstrator: A miniaturized reconfigurable front-end**

Demonstrator #2 (Thales Alenia Space Italy) Multi-band re-configurable receiver Hybrid integration on LTCC

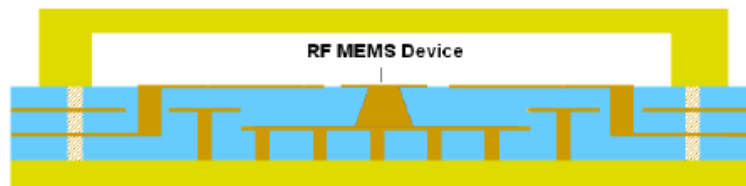
- u GaN amplifiers on LTCC (C- & X-band)
- u RF-MEMS SPDT & 2x2 matrix on LTCC substrates



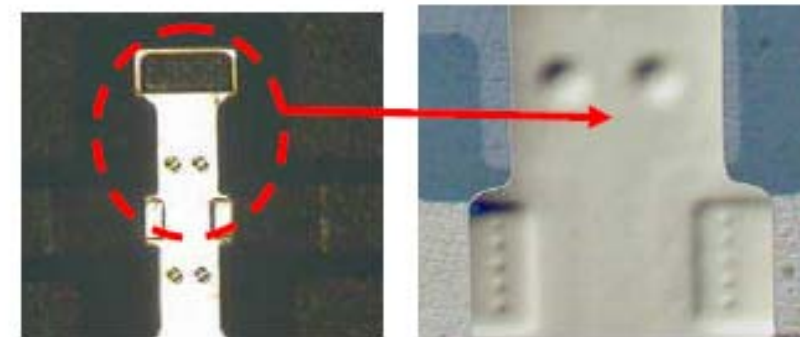
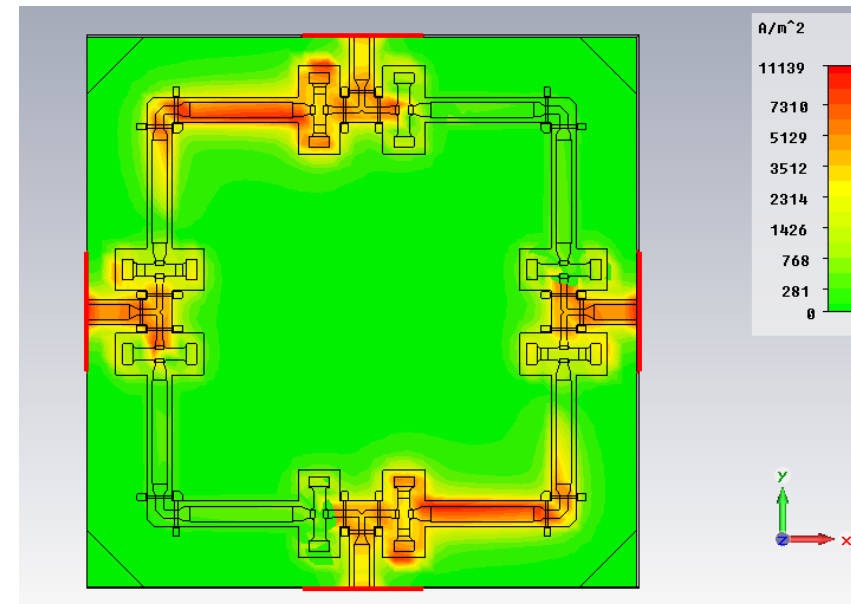
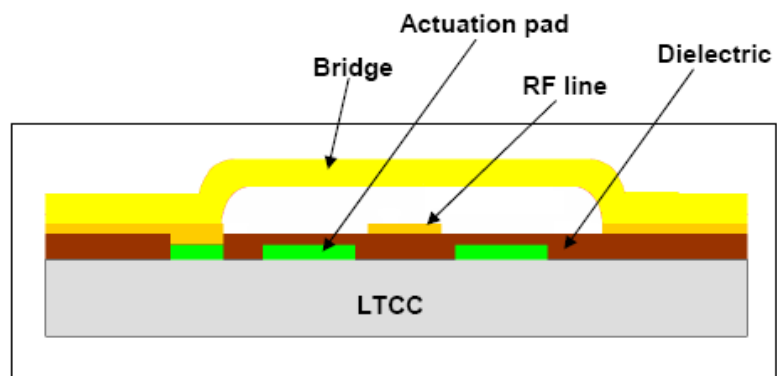
RF-MEMS on LTCC



Silicon MEMS chip glued in a LTCC package with internal wire transitions



Integration of the MEMS directly on the LTCC substrate



The electrostatic actuation of the bridge is obtained by means of two resistive metallic pads (made of NiCr or TaN). The actuation pads are covered with a dielectric layer (polyimide).

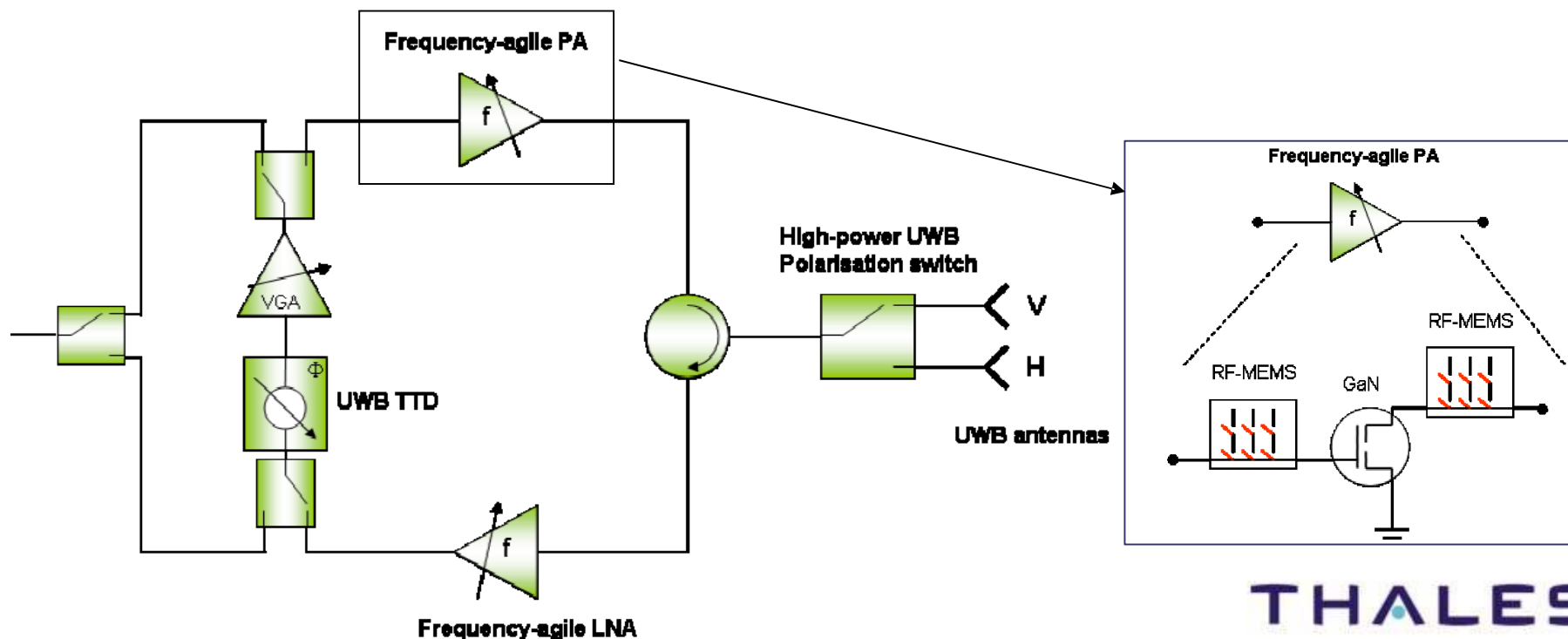
Hybrid and monolithic integration approaches

- u **Re-configurable RF-MEMS based matching networks and high-power SPDT switches will be designed and manufactured on Silicon and on GaN**
- u **These circuits will then be integrated with the GaN high-power and low-noise transistors on a LTCC RF-board**
- u **Ultra-high performance true-time-delay (TTD) units**

▷ **3rd demonstrator: Re-configurable frequency-agile T/R module**

Demonstrator #3 (EADS)
Reconfigurable frequency-agile T/R-module
Hybrid integration on multilayer LTCC board

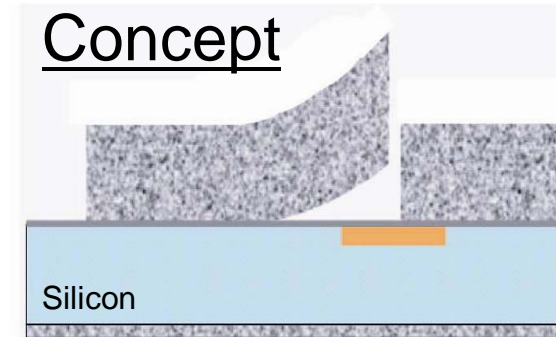
- u GaN-based amplifiers (from L- to Ku-band)
- u Si-based RF-MEMS SPDT



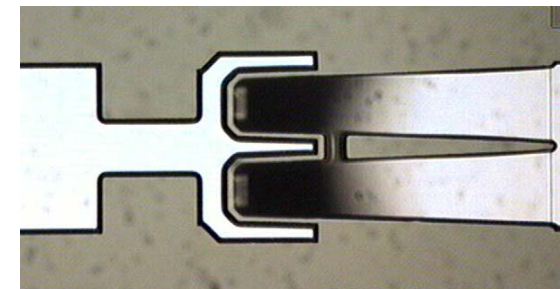
RF-MEMS switches on Si

- u high-resistivity silicon substrate
thermally grown silicon oxide
Implantation layer for capacitive coupling
only 3 lithography process steps
- u substrate thickness: 100 μ m
black parts are bended upwards
design focus on low-frequency behaviour
- u Frequency-range: 1.8 - 10GHz
Insertion loss: < -0.6dB
Isolation:> -26dB

Concept



Fabricated switch



Measurement results

